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APJ ABDUL KALAM TECHNOLOGICAL UNIVERSITY

B.Tech Degree S3 (R,S) / S3 (WP) (R,S) / S1 (PT) (S,FE) Examination November 2024 (2019 Scheme)



Course Code: ECT201

Course Name: SOLID STATE DEVICES

Max. Marks: 100

Duration: 3 Hours

PART A

Answer all questions. Each question carries 3 marks

Marks

- 1 What is an extrinsic semiconductor? How is it produced from an intrinsic semiconductor? (3)
- 2 Write the expression for Fermi-Dirac distribution function. Plot the Fermi-Dirac distribution function verses the energy band diagram of n-type and p-type semiconductor. (3)
- 3 Distinguish between lattice scattering and ionized impurity scattering. (3)
- 4 The hole mobility of a semiconductor $\mu_p = 500 \text{ cm}^2/\text{Vs}$, $kT/q = 26\text{mV}$ and $\tau_p = 0.1 \mu\text{s}$. Find the diffusion constant (D_p) and diffusion length (L_p) at 300K? (3)
- 5 Draw the energy band diagram of forward and reverse bias PN junction. (3)
- 6 What is meant by electron affinity and work function? (3)
- 7 What is the strong inversion with reference to a MOS capacitor (3)
- 8 What is the difference between enhancement and depletion MOSFET? (3)
- 9 Explain the need for scaling? (3)
- 10 How does channel length modulation affect the drain characteristics of a MOSFET? (3)

PART B

Answer any one full question from each module. Each question carries 14 marks

Module 1

- 11a. Derive the equation for electron and hole concentration in a semiconductor at equilibrium Find how these concentrations are related to intrinsic carrier concentration. (9)
- b. A Si sample is doped with 10^{16} Phosphorous atoms/cm³. Calculate the equilibrium hole concentration p_0 at 300K. Find the location of E_F relative to (5)

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E_i ? Draw the energy band diagram of the same. What changes occur in energy band diagram if phosphorus doping is increased? What does this imply? (Take $n_i = 1.5 \times 10^{10} \text{ cm}^{-3}$)

- 12a. Explain the different types of indirect recombination mechanisms in a semiconductor. How do they differ from direct recombination? (8)
- b. Consider Si doped with $2 \times 10^{15} \text{ donors/cm}^{-3}$, and assume that $\tau_n = \tau_p = 5 \mu\text{s}$. Calculate the recombination coefficient, α_r for the low-level excitation, and find the steady state excess carrier concentration $\Delta n = \Delta p$, if the sample is uniformly exposed to a steady state optical generation rate $g_{op} = 10^{19} \text{ EHP/cm}^3\text{s}$. (6)

Module 2

- 13a. Derive the equation for the drift current in a semiconductor. (10)
- b. Derive Poisson's equation. (4)
- 14a. What is Hall effect? Derive the expression for carrier concentration and mobility in terms of Hall voltage. (8)
- b. A Ge sample is properly contacted and oriented in a $5 \times 10^{-5} \text{ Wb/cm}^2$ magnetic field and the current is 4 mA. The sample dimensions are $w = 0.25\text{mm}$, $t = 50 \mu\text{m}$ and $L = 2.5\text{mm}$ and the measurements are $V_{AB} = -2.5 \text{ mV}$ and $V_{CD} = 170 \text{ mV}$. Find the type and concentration of majority carriers and its mobility? (6)

Module 3

- 15a. Derive the expression for maximum value of electric field and depletion width of an abrupt PN junction at equilibrium. Plot the electric field distribution and potential distribution across the depletion region. (10)
- b. Draw the energy band diagram of metal n-type semiconductor Schottky contact. (4)
- 16a. With suitable assumptions derive the expression of the ideal diode equation. Plot the minority carrier distribution across the p-n junction in forward bias condition. (10)
- b. What is base width modulation? How does it affect the terminal currents of a BJT.? (4)

Module 4

17. With the aid of necessary band diagrams, explain equilibrium, accumulation, depletion and inversion stages of a MOS capacitor. Find the expression for threshold voltage of an ideal MOS capacitor. (14)
- 18a. Derive the expression for drain current in linear and saturation region. (10)

- b. A Si n-channel MOSFET with n^+ polysilicon gate has $V_{GS} = 3\text{ V}$, $V_{DS} = 5\text{ V}$, $V_T = 0.76\text{ V}$, $t_{ox} = 300\text{ \AA}$, $\mu_n = 600\text{ cm}^2/\text{Vs}$, $z = 50\text{ }\mu\text{m}$, $L = 10\text{ }\mu\text{m}$, and $C_{ox} = 1.15 \times 10^{-7}\text{ F/cm}^2$. Calculate the drain current. (4)

Module 5

- 19a. Explain the concept of constant field scaling. What are the advantages compared to constant voltage scaling? (8)
- b. How does hot carrier effect affect the performance of a short channel MOSFET? (6)
- 20 With suitable diagram explain the working of FinFET? How does the structure help in enhancing MOSFET performance (14)
